

ABSTRACT

The present disclosure relates to a cleaning composition and a method for removing polymer film bonding materials using the same, especially for removing
5 siloxane polymer bonding materials, wherein the cleaning composition at least comprises tetraalkylammonium fluoride (weight percentage concentration: 0.1%-15%), alkyl amide (weight percentage concentration: 20%-95%), aromatic ether (weight percentage concentration: 1%-80%) and water.

[No Fig.]